



10-15-04

IFW

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. .... 10/664,744  
Filing Date ..... September 18, 2003  
Inventor..... Michael T. Andreas  
Assignee ..... Micron Technology, Inc.  
Group Art Unit ..... 2823  
Examiner ..... Fernando L. Toledo  
Attorney's Docket No. ..... MI22-2711  
Title .... Method of Polishing a Semiconductor Substrate, Post-CMP Cleaning Process, and Method of Cleaning Residue from Registration Alignment Markings (As Amended)

**RESPONSE TO SEPTEMBER 23, 2004 OFFICE ACTION**

To: Mail Stop Amendment  
Commissioner for Patents  
P. O. Box 1450  
Alexandria, VA 22313-1450

**VIA EXPRESS MAIL**

From: Mark S. Matkin (Tel. 509-624-4276; Fax 509-838-3424)  
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601 West First Avenue, Suite 1300  
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Responsive to the Office Action dated September 23, 2004, Applicant amends and remarks as follows:

**AMENDMENTS**

**In the Title**

Please replace the title with:

--Method of Polishing a Semiconductor Substrate, Post-CMP Cleaning Process, and Method of Cleaning Residue from Registration Alignment Markings--.